L Number	Hits	Search Text	DB	Time stamp
-	2492	(exposure adj apparatus) and lithography	USPAT;	2004/02/18 16:28
			US-PGPUB;	
			EPO; JPO;	
			IBM_TDB	
	1852	((exposure adj apparatus) and lithography) and stage	USPAT;	2004/02/18 16:29
İ	1032	((exposure daj apparatas) and natiography) and stage	US-PGPUB;	2001/02/10 10:23
			EPO; JPO;	
			IBM_TDB	
1	1702	(//averaging adj apparents) and lithography) and stage) and	_	2004/02/10 16:20
-	1783	(((exposure adj apparatus) and lithography) and stage) and	USPAT;	2004/02/18 16:29
:		(mask or reticle)	US-PGPUB;	
			EPO; JPO;	
			IBM_TDB	
-	2134	((exposure adj apparatus) and lithography) and (stage or	USPAT;	2004/02/18 16:29
		table)	US-PGPUB;	
			EPO; JPO;	
			IBM_TDB	
·	2020	(((exposure adj apparatus) and lithography) and (stage or	USPAT;	2004/02/18 16:29
		table)) and (mask or reticle)	US-PGPUB;	
			EPO; JPO;	
			IBM_TDB	
]_	1362	((((exposure adj apparatus) and lithography) and (stage or	USPAT;	2004/02/18 16:30
	1002	table)) and (mask or reticle)) and illumination	US-PGPUB;	200 ,, 02, 20 20 10 10
		table)) and (mask of Fodeloy) and mammation	EPO; JPO;	
			IBM_TDB	
	1342	(((((exposure adj apparatus) and lithography) and (stage or	USPAT;	2004/02/18 16:31
-	1342		US-PGPUB;	2004/02/10 10.31
		table)) and (mask or reticle)) and illumination) and (wafer or		
		specimen or sample)	EPO; JPO;	
	470		IBM_TDB	2004/02/40 46:22
-	170	((((((exposure adj apparatus) and lithography) and (stage or	USPAT;	2004/02/18 16:32
		table)) and (mask or reticle)) and illumination) and (wafer or	US-PGPUB;	
		specimen or sample)) and (reaction near4 force)	EPO; JPO;	
			IBM_TDB	
-	206	(((exposure adj apparatus) and lithography) and (stage or	USPAT;	2004/02/18 16:32
		table)) and (reaction near4 force)	US-PGPUB;	
			EPO; JPO;	
		·	IBM_TDB	
-	118	((((((exposure adj apparatus) and lithography) and (stage	USPAT;	2004/02/18 16:32
		or table)) and (mask or reticle)) and illumination) and (wafer	US-PGPUB;	
		or specimen or sample)) and (reaction near4 force)) and	EPO; JPO;	
		electromagnetic	IBM_TDB	
-	100	(((((((exposure adj apparatus) and lithography) and (stage	USPAT;	2004/02/18 16:33
		or table)) and (mask or reticle)) and illumination) and (wafer	US-PGPUB;	, ,
		or specimen or sample)) and (reaction near4 force)) and	EPO; JPO;	
		electromagnetic) and magnet	IBM_TDB	
_	9	((((((((((((((((((((((((((((((((((((((	USPAT;	2004/02/18 16:48
	,	((((((((((((((((((((((((((((((((((((((	US-PGPUB;	
		(wafer or specimen or sample)) and (reaction near4 force))	EPO; JPO;	
		and electromagnetic) and magnet) and (driver or mover)	IBM_TDB	
			םטו_וטט	
	24	and stator) and (magnetic adj pole)	LICDAT	2004/02/19 16:50
-	24	(((((((((exposure adj apparatus) and lithography) and	USPAT;	2004/02/18 16:50
		(stage or table)) and (mask or reticle)) and illumination) and	US-PGPUB;	
		(wafer or specimen or sample)) and (reaction near4 force))	EPO; JPO;	
		and electromagnetic) and magnet) and (driver or mover) )	IBM_TDB	
	_ :=	and stator		
-	56	((((((((exposure adj apparatus) and lithography) and (stage	USPAT;	2004/02/24 13:54
		or table)) and (mask or reticle)) and illumination) and (wafer	US-PGPUB;	
[		or specimen or sample)) and (reaction near4 force)) and	EPO; JPO;	
		electromagnetic) and magnet) and (driver or mover)	IBM_TDB	

			2004/00/04/05
-	5   ((((((((exposure adj apparatus) and lithography) and	USPAT;	2004/02/24 13:55
Ì	(stage or table)) and (mask or reticle)) and illumination) and	US-PGPUB;	
	(wafer or specimen or sample)) and (reaction near4 force))	EPO; JPO;	
	and electromagnetic) and magnet) and (driver or mover))	IBM_TDB	
1	and canceling		